

Ota

SUBSTITUTE FOR MISSING XR

[54] ELECTROPHORETIC LIGHT IMAGE
REPRODUCTION PROCESS

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[22] Filed: Apr. 15, 1970

[21] Appl. No.: 28,587

[52] U.S. Cl. 96/1 R, 96/1.2, 96/1.3,
96/1.5, 204/181 PE

[51] Int. Cl. G03g 5/00, G03g 13/00

[58] Field of Search 96/1, 1.2, 1.5, 1.3;
204/181 PE

[56]

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[57] ABSTRACT

Electrophoretic light image reproduction process is disclosed in which a D.C. voltage is applied to a double layer of a photoconductive layer and an electrophoretic suspension layer including a dispersion of at least one electrophoretic material in a finely divided powder form suspended in a suspending medium, whereby said D.C. voltage changes the optical reflective property of said electrophoretic suspension layer due to electrophoretic movement of said electrophoretic material, said photoconductive layer is exposed to a light image so that the light-struck area has a low electrical resistance, an electric field is applied to said double layer having said electrophoretic suspension layer changed in the optical reflective property and having said photoconductive layer lowered in the electrical resistance at the light-struck area, whereby said electrophoretic material at said light-struck area moves electrophoretically and reproduces said light image on said electrophoretic suspension layer.

18 Claims, 12 Drawing Figures

